

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yiming Gu et al.

Practitioner's Docket No.: IDT-1769

Filing Date: 3/25/2004

For: METHOD FOR DETERMINING PHOTORESIST
THICKNESS AND STRUCTURE FORMED USING
DETERMINED PHOTORESIST THICKNESS

Serial No.: 10/808,806

Examiner: Young

Art Unit: 1756

Confirmation No. 7586

Commissioner for Patent

P.O. Box 1450

Alexandria, VA 22313-1450

Amendment After Notice of Allowance

(37 C.F.R. § 1.312)

Dear Sir:

Applicants request that the present amendments be entered.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 8 of this paper.